ECE 340: Semiconductor Electronics

Chapter 3: Energy bands and charge carriers in semiconductors (part III)

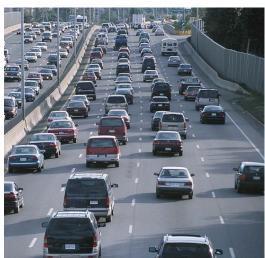
Wenjuan Zhu

Outline

- Drift of carriers in electric and magnetic fields
- Conductivity and mobility
 - Drift and resistance
 - Effect of temperature and doping on mobility
- Invariance of the Fermi level at equilibrium

Factors that influence current or cargo flow





Number of the carriers



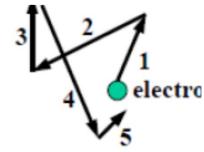


Carrier velocity (how mobile they are, interruptions on the road)

Thermal velocity

- In thermal equilibrium, carriers are not sitting still, but rather move about with random velocities.
- The mean-square thermal velocity of the electrons is related to temperature by:

$$\frac{1}{2}m_n^* v_{th}^2 = \frac{3}{2}kT$$



 m_n^* is the effective mass of conduction-band electrons k: Boltzmann's constant

- At T=300K: $v_{th} = 2.3 \times 10^7 cm \cdot s^{-1}$
- The net current in any direction is zero, if no electric field is applied

Carrier Scattering in thermal motion

- Mobile electrons in Silicon lattice move in random directions with many collisions:
 - collide with the lattice
 - collide among themselves
 - scatter by ionized impurity atoms
- Mean free time between collision: τ_{cn}

Mean free path

• Mean free path, characteristic length of thermal motion:

$$\lambda = v_{th} \tau_{cn}$$

• For Si at 300K:

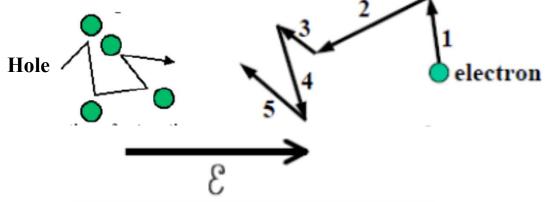
$$\tau_{cn} \approx 10^{-14} \sim 10^{-13} s$$

$$v_{th} \approx 2.3 \times 10^7 cm \cdot s^{-1}$$

$$\lambda \approx 1 \sim 10 nm$$

Carrier Motion in Electric Field

- If apply a small electric field to the lattice:
 - Holes move in the direction of the electric field
 - Electrons move in the opposite direction of the electric field
- Motion is highly non-directional on a local scale, but has a net direction on a macroscopic scale.
- Net motion of charged particles give rise to a current.



Acceleration and deceleration process

Acceleration by electric field:

$$-nq\mathcal{E} = \frac{dP_x}{dt}$$

Deceleration due to collisions:

$$-\frac{dN(t)}{dt} = \frac{1}{\tau}N(t) \qquad \Box > N(t) = N_0 \ e^{-t/\tau}$$

$$dP_{x} = -P_{x} \frac{dt}{\tau}$$

• At steady state, the sum of acceleration and deceleration effects is zero:

$$-nq\mathcal{E} - \frac{P_{x}}{\tau} = 0$$

Average momentum per electron: $\langle p_x \rangle = \frac{P_x}{n} = -q\tau \mathcal{E}$

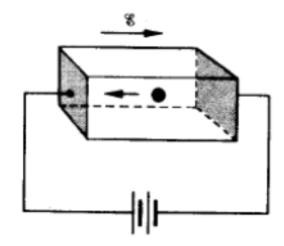
Drift Velocity

• Drift velocity: the average net velocity, v_d [cm/s].

$$V_d = \frac{\langle p_x \rangle}{m^*}$$

$$\Longrightarrow_{\text{Electron}} v_{d_n} = -\frac{q \tau_{cn}}{m_n^*} \mathcal{E}$$

Hole
$$oldsymbol{v_{d_p}} = rac{q au_{cp}}{m_p^*} \mathcal{E}$$



Mobility

Define mobility:

$$\mu_n = rac{q au_{cn}}{m_n^*}$$
 Electron mobility $\mu_p = rac{q au_{cp}}{m_n^*}$ Hole mobility

 Mobility can also be expressed as the average particle drift velocity per unit electric field:

$$\mu_n = -\frac{v_{d_n}}{\mathcal{E}}$$

$$\mu_p = \frac{v_{d_p}}{\mathcal{E}}$$

Mobility describes how strongly the motion of an electron is influenced by an applied field.

Electron and hole mobility

$$\mu$$
 has the dimension of v/\mathcal{E} , unit: $\left[\frac{cm/s}{V/cm} = \frac{cm^2}{V \cdot s}\right]$

Electron and hole mobilities of some undoped (intrinsic) semiconductors at room temperature:

	Si	Ge	GaAs	InAs
$\mu_n \text{ (cm}^2/\text{V}\cdot\text{s)}$	1400	3900	8500	30000
$\mu_p \text{ (cm}^2/\text{V}\cdot\text{s)}$	470	1900	400	500

Mobility is measure of ease of carrier drift:

$$\mu = \frac{q \boldsymbol{\tau_c}}{m^*}$$

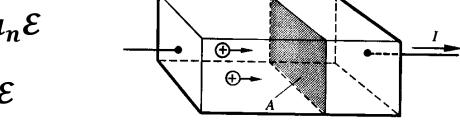
- If $\tau_c \uparrow$, longer time between collisions $\rightarrow \mu \uparrow$
- If $m^* \downarrow$, "lighter" particle $\rightarrow \mu \uparrow$

Current Density

 The electron current density flowing in the direction of the applied field:

Electron:
$$J_n = -qnv_{d_n} = qn\mu_n \mathcal{E}$$

Hole:
$$J_p = qpv_{d_p} = qp\mu_p \mathcal{E}$$



$$\frac{ampere}{cm^2} = coulomb \cdot \frac{1}{cm^3} \frac{cm}{s}$$

Conductivity

Total current including both electron and hole:

$$J = q(n\mu_n + p\mu_p)\mathcal{E}$$

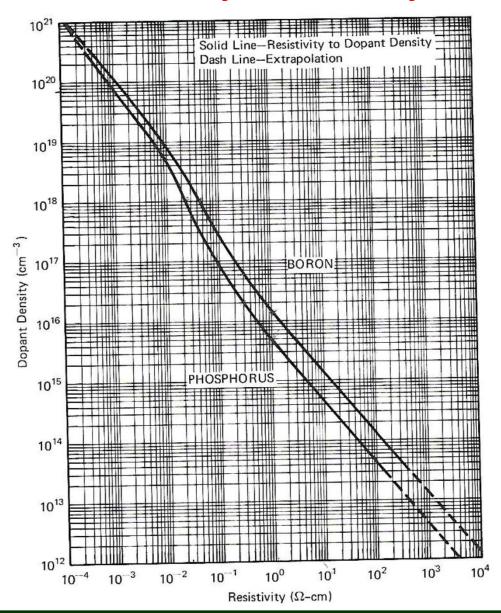
Define conductivity:

$$\sigma = J/\mathcal{E}$$

Impact of doping on conductivity/resistivity

- Conductivity: $\sigma = J/\mathcal{E}$
- Resistivity: $\rho = \mathcal{E}/J = \frac{1}{\sigma}$
- Conductivity increase with increasing carrier concentration

$$\sigma = q(n\mu_n + p\mu_p)$$



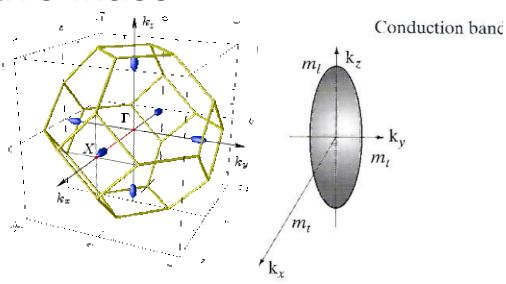
• For a piece of P-type piece of silicon at 300K, its conductivity is 4 Ω^{-1} cm⁻¹, assuming the P-type silicon has μ_n = 1200 cm²/V-s and μ_p = 300 cm²/V-s, calculate the hole and electron concentration

 Ex: What is the hole drift velocity at room temperature in silicon, in a field £ = 1000 V/cm? What is the average time and distance between collisions?

Effective Mass

1. Band curvature Effective Mass:

$$m^* = \frac{\hbar^2}{d^2 E/dk^2}$$



2. Density of State Effective Mass:

$$m_{n_DOS}^* = 6^{2/3} (m_l m_t^2)^{1/3}$$

For density of state and carrier concentration calculation

$$N_C = 2 \left(\frac{2\pi m_n^* kT}{h^2} \right)^{3/2}$$

3. Conductivity Effective Mass:

$$\frac{1}{m_{n_cond}^*} = \frac{1}{3} \left(\frac{1}{m_l} + \frac{2}{m_t} \right)$$

For conductivity calculation

$$\mu = \frac{q \boldsymbol{\tau_c}}{m^*}$$

Effective mass and energy bandgap of Ge, Si and GaAs

Name	Symbol	Germanium	Silicon	Gallium Arsenide
Smallest energy bandgap at 300 K	$E_{\rm g} ({\rm eV})$	0.66	1.12	1.424
Effective mass for density of states calculations				
Electrons	$m_{\rm e}^*, dos/m_0$	0.56	1.08	0.067
Holes	$m_{\rm h}^*, dos/m_0$	0.29	0.57/0.812	0.47
Effective mass for conductivity calculations				
Electrons	$m_{\rm e}^*, {\rm cond}/m_0$	0.12	0.26	0.067
Holes	$m_{\rm h}^*, {\rm cond}/m_0$	0.21	$0.36/0.386^2$	0.34

 $m_0 = 9.11 \text{ x } 10^{-31} \text{ kg}$ is the free electron rest mass.

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Drift and resistance

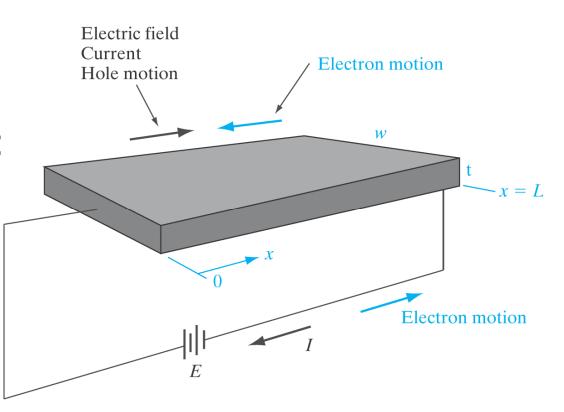
• Ohm's Law

$$I=\frac{V}{R}$$

Resistance of the bar:

$$R = \rho \frac{L}{wt}$$

$$\rho = \frac{1}{\sigma} = \frac{1}{q(n\mu_n + p\mu_p)}$$

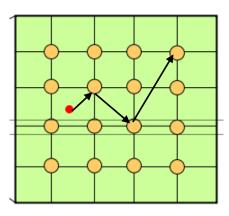


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Scattering and mobility

- Two basic types of scattering mechanism that influence mobility:
 - Lattice scattering



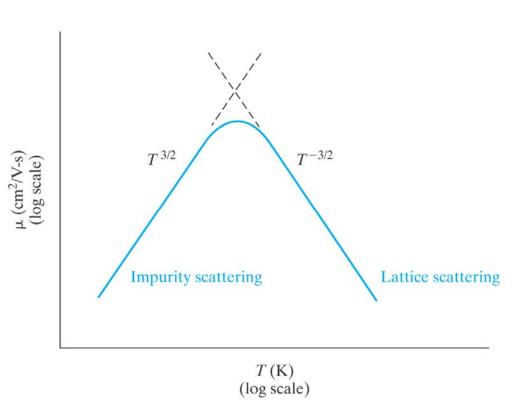
Impurity scattering





Temperature dependence of mobility

- As T increase, thermal agitation of the lattice increases, the frequency of lattice scattering event increases → mobility limited by lattice scattering decrease
- At T decrease, thermal motion of the carrier is slower, carrier is scattered more strongly by an charged ion → mobility limited by impurity scattering decrease



Matthiessen Rule

• The total probability of a carrier is scattered in the time interval dt is the sum of probability of being scattered by each mechanism:

$$\frac{dt}{\tau_c} = \sum_{i} \frac{dt}{\tau_i}$$

 Therefore the mobility due to two or more scattering mechanisms is:

$$\frac{1}{\mu} = \frac{1}{\mu_1} + \frac{1}{\mu_2} + \cdots$$

 The mechanism causing the lowest mobility value dominants.

Effect of impurity concentration on mobility

- Higher the doping concentration,
- →higher the impurity scattering rate
- → lower mobility

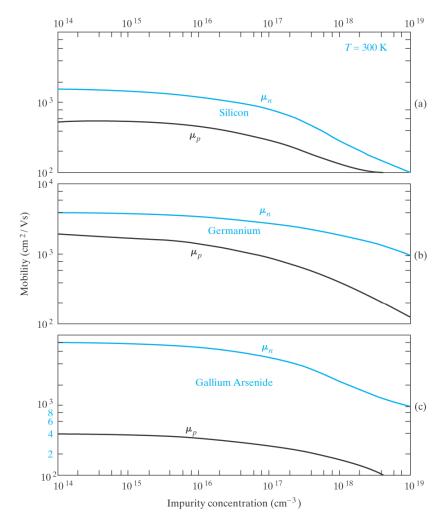
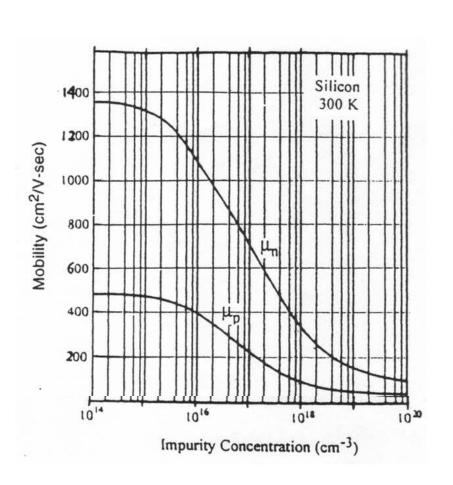
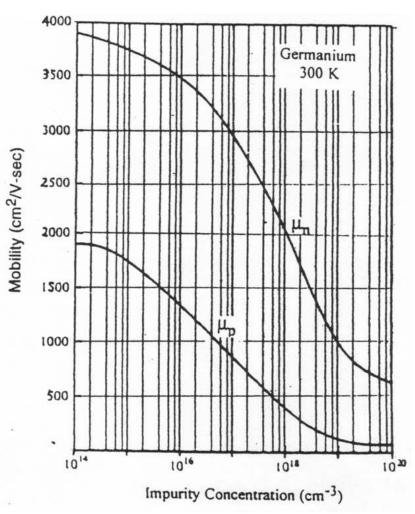


Figure 3.23

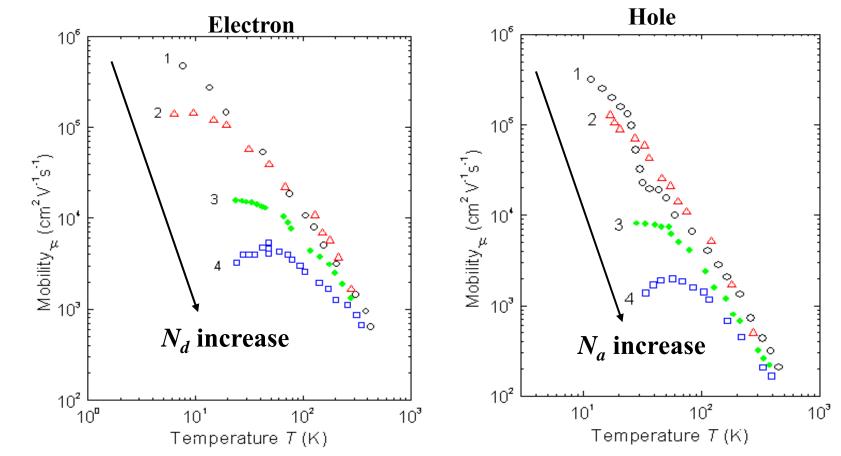
Variation of mobility with total doping impurity concentration $(N_a + N_d)$ for Ge, Si, and GaAs at 300 K.

• In linear scale, from the ECE 340 course web site:





Mobility versus temperature for different doping levels



- Impurity $\uparrow \rightarrow \mu \downarrow$, due to impurity scattering;
- At low T, $T \uparrow \rightarrow \mu \uparrow$ due to impurity scattering; At high T, $T \uparrow \rightarrow \mu \downarrow$ due to lattice scattering;

Resistivity dependence on doping

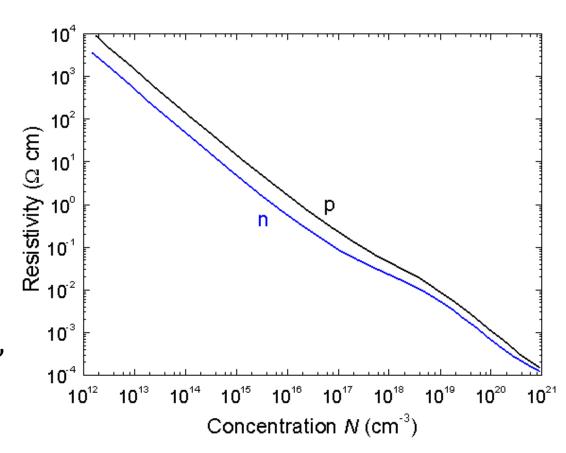
For n type material:

$$oldsymbol{
ho}=rac{1}{qn\mu_n}$$

• For p type material:

$$oldsymbol{
ho}=rac{1}{qp\mu_p}$$

- Doping $\uparrow \rightarrow n$ (or p) \uparrow , $(\mu \downarrow \text{slightly}) \rightarrow \rho \downarrow$
- We have control over resistivity via doping!



Note: this plot do not apply to compensated material

 Ex: What is the hole drift velocity at room temperature in silicon, in a field £ = 1000 V/cm? What is the average time and distance between collisions?

Hint:

	Si	Ge	GaAs	InAs
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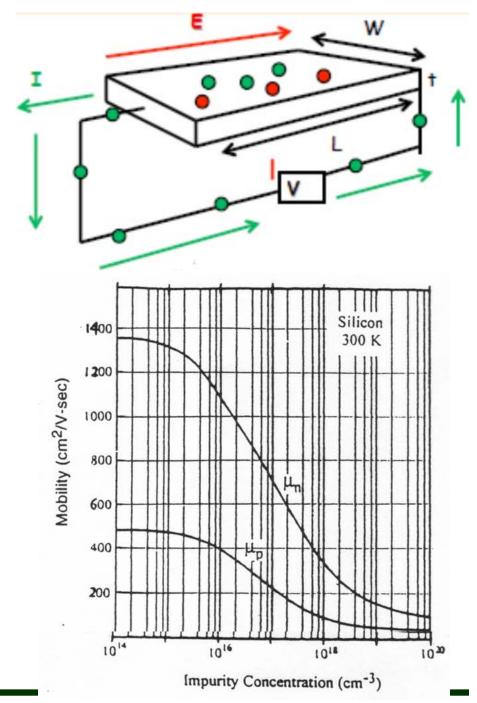
Consider a Si sample doped with 10¹⁶/cm³ Boron. What is its resistivity?

Consider the same Si sample, doped additionally with 10¹⁷/cm³ Arsenic. What is its resistivity?

Consider a silicon bar

L=0.1cm A=100 µm² Nd=10¹⁷cm⁻³

Find the current with 10V applied at 300K

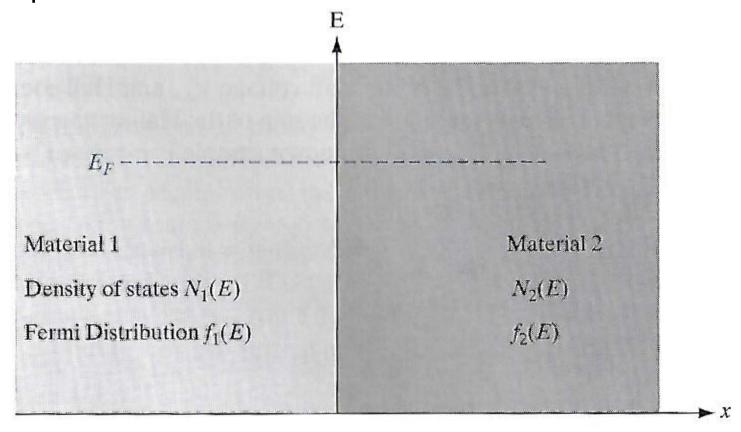


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- →• Invariance of the Fermi level at equilibrium

Fermi level invariance

- Invariance of the Fermi level at equilibrium
 - No discontinuity or gradient can arise in the equilibrium Fermi level



Fermi level invariance

At energy E the rate of transfer of electrons is:

rate from 1 to 2
$$\propto N_1(E)f_1(E) \cdot N_2(E)[1 - f_2(E)]$$

rate from 2 to 1 $\propto N_2(E)f_2(E) \cdot N_1(E)[1 - f_1(E)]$

At equilibrium, there is no current, i.e. no net charge transport, no net transfer of energy:

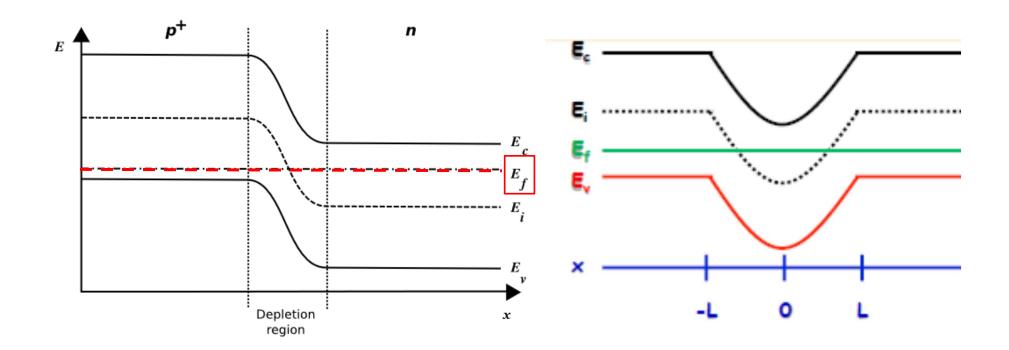
$$N_1(E)f_1(E) \cdot N_2(E)[1 - f_2(E)] = N_2(E)f_2(E) \cdot N_1(E)[1 - f_1(E)]$$

$$\longrightarrow$$
 $E_{F1} = E_{F2}$

More generally:

$$\frac{dE_F}{dx}=0$$

Example energy diagram at equilibrium



• At equilibrium, Fermi level is **FLAT**, i.e. no gradient.